

This listing of claims will replace prior versions, and listings, of claims in the application:

Listing Of Claims:

- 1 1. (Currently Amended) Apparatus for automatically measuring the surface properties of optical elements, said apparatus comprising:
 - 3 a support for an element having at least one test surface to be measured;
 - 4 means for generating an output beam having a predetermined wavefront profile;
 - 5 a measurement plane;
 - 6 means for controllably translating said output beam along an optic axis with respect to said support so that said predetermined wavefront profile thereof impinges on said element from a predetermined direction and then is reflected to travel opposite said predetermined direction as a distorted wavefront containing distortions that vary in accordance with the topography of said test surface and the position of said output beam along said optic axis; and
 - 12 means for sampling said distorted wavefront profile at predetermined locations thereover, each of which said predetermined locations corresponds to a discrete portion of said distorted wavefront, as said output beam is translated relative to said test surface, focusing each of said discrete portions to a spot in said measurement plane, determining the two-dimensional deviation of said spots away from their anticipated focal point in said measurement plane, and determining the local deformation of said distorted wavefront based on said deviations everywhere corresponding to a sampled location on said test surface and the position of said output beam with respect to said test surface along said optic axis.
- 1 2. (Original) The apparatus of claim 1 further including analytical means for representing the topography of said test surface with a mathematical approximation comprising a series of coefficients and variables; calculating the value of said coefficients based on the local deformation of said wavefront at at least one position of said source with respect to said test surface.
- 1 3. (Original) The apparatus of claim 2 wherein said analytical means includes means for performing an optimization analysis using the values of said coefficients

3 calculated for each position of said source and test surface to arrive at a final value for
4 said coefficients that are used for said mathematical approximation to represent the
5 shape of said surface to a predetermined accuracy.

4. (Original) The apparatus of claim 1 wherein said predetermined wavefront comprises a plane wavefront.

5. (Original) The apparatus of claim 1 wherein said predetermined wavefront comprises a nominally spherical wavefront.

6. (Original) The apparatus of claim 1 wherein said means for generating said output beam comprises a light source and collimating optics.

7. (Original) The apparatus of claim 6 further including a well-corrected objective lens.

8. (Original) The apparatus of claim 1 further including a positive lens located in a fixed position with respect to said support and along said predetermined direction to facilitate the measurement of parts having long radii of curvature.

9. (Original) The apparatus of claim 4 further including a reflective means positioned with respect to said support to facilitate the measurement of transmitted wavefront errors in optical bandpass components including filters and windows.

10. (Original) The apparatus of claim 9 further including a relay section.

11. (Original) The apparatus of claim 4 further including a beam expansion section.

12. (Original) The apparatus of claim 1 wherein said means for sampling said distorted wavefront comprises a two-dimensional lens array and a two-dimensional photodetector array having discrete sensing elements.

13. (Original) The apparatus of claim 12 wherein said two-dimensional lens array comprises a pair of crossed lenticular screens with index mismatching material between them.

14. (Original) The apparatus of claim 12 wherein said means for generating said output beam comprises a microscope objective lens and further including a telescopic section between said microscope objective lens and said two-dimensional lens array to image said two-dimensional photodetector array into the pupil of said microscope objective lens.

1 15. (Currently Amended) Apparatus for automatically measuring the properties of surfaces that are at least partially specularly reflective, said apparatus comprising:
2 a support for an element having at least one test surface to be measured;
3 a source having an output with a predetermined wavefront profile;
4 a measurement plane;
5 means for controllably moving said source and said support relative to one another along an optic axis so that a test surface in said support continuously reflects said output from said source back towards said source while distorting said wavefront profile thereof in accordance with the topography of said test surface and the relative position of said source with respect to said test surface along said optic axis; and
6 means for sampling said distorted wavefront profile at predetermined locations thereover, each of which said predetermined locations corresponds to a discrete portion of said distorted wavefront profile, as said source is moved relative to said test surface along said optic axis; focusing each of said discrete portions to a spot in said measurement plane, determining the two-dimensional deviation of said spots away from their anticipated focal point in said measurement plane, and determining the local deformation of said distorted wavefront profile based on said deviations everywhere corresponding to a sampled location on said test surface and the position of said source with respect to said test surface along said optic axis.

16. (Original) The apparatus of claim 15 further including analytical means for representing the topography of said test surface with a mathematical approximation comprising a series of coefficients and variables; calculating the value of said coefficients based on the local deformation of said wavefront at at least one position of said source with respect to said test surface;

17. (Original) The apparatus of claim 15 wherein said analytical means includes means for performing an optimization analysis using the values of said coefficients calculated for each position of said source and test surface to arrive at a final value for said coefficients that are used for said mathematical approximation to represent the shape of said surface to a predetermined accuracy.

18. (Original) The apparatus of claim 1 wherein said means for sampling said distorted wavefront profile comprises a two-dimensional lenslet array having a focal plane and a one-dimensional photodetector array arranged to scan across said focal plane.

19. (Original) The apparatus of claim 1 wherein said means for generating an output beam comprises one of a pulsed light source or strobe.

1 20. (Currently Amended) A method for automatically measuring the surface
2 properties of optical elements, said method comprising the steps of:
3 supporting an element having at least one test surface to be measured;
4 generating an output beam having a predetermined wavefront profile;
5 providing a measurement plane;
6 controllably translating said output beam with respect to said support along an
7 optic axis so that said predetermined wavefront profile thereof impinges on said element
8 from a predetermined direction and then is reflected to travel opposite said
9 predetermined direction as a distorted wavefront containing distortions that vary in
10 accordance with the topography of said test surface and the position of said output beam
11 along said optic axis; and

12 sampling said distorted wavefront profile at predetermined locations thereover,
13 each of which said predetermined locations corresponds to a discrete portion of said
14 distorted wavefront, as said output beam is moved relative to said test surface along
15 said optic axis, focusing each of said discrete portions to a spot in said measurement
16 plane, determining the two-dimensional deviation of said spots away from their
17 anticipated focal points in said measurement plane, and determining the local
18 deformation of said distorted wavefront based on said deviations everywhere
19 corresponding to a sampled location on the test surface and the position of said output
20 beam with respect to said test surface along said optic axis.

21. (Original) The method of claim 20 further including the step of analytically representing the topography of said test surface with a mathematical approximation comprising a series of coefficients and variables and calculating the value of said coefficients based on the local deformation of said wavefront at at least one position of said source with respect to said test surface.

1 22. (Currently Amended) Apparatus for automatically measuring the surface
2 properties of optical elements, said apparatus comprising:
3 a support for an element having at least one test surface to be measured;
4 means for generating an output beam having a predetermined plane wavefront
5 profile;
6 a measurement plane;
7 means for controllably positioning said output beam with respect to said support
8 so that said predetermined wavefront profile thereof impinges on said element from a
9 predetermined direction and then is reflected to travel opposite said predetermined
10 direction as a distorted wavefront containing distortions that vary in accordance with the
11 topography of said test surface and the position of said output beam;
12 means for sampling said distorted wavefront profile at predetermined locations
13 thereover, each of which said predetermined locations corresponds to a discrete portion
14 of said distorted wavefront, as said output beam is moved relative to said test surface,
15 focusing each of said discrete portions to a spot in said measurement plane, determining
16 the two-dimensional deviation of said spots away from their anticipated focal points in

17 said measurement plane, and determining the local deformation of said distorted
18 wavefront based on said deviations everywhere corresponding to a sampled location
19 and the position of said output beam with respect to said test surface; and
20 reflective means positioned with respect to said support to facilitate the
21 measurement of transmitted wavefront errors in optical bandpass components including
22 filters and windows.

23. (Previously presented) The apparatus of claim 22 further including a relay section.

1 24. (Previously presented) Apparatus for automatically measuring the surface
2 properties of optical elements, said apparatus comprising:
3 a support for an element having at least one test surface to be measured;
4 means for generating an output beam having a predetermined wavefront profile;
5 means for controllably positioning said output beam with respect to said support
6 so that said predetermined wavefront profile thereof impinges on said element from a
7 predetermined direction and then is reflected to travel opposite said predetermined
8 direction as a distorted wavefront containing distortions that vary in accordance with the
9 topography of said test surface and the position of said output beam; and
10 a two-dimensional lens array comprising a pair of crossed lenticular screens with
11 index mismatching material between them, and a two-dimensional photodetector array
12 having discrete sensing elements for sampling said distorted wavefront profile at
13 predetermined locations thereover as said output beam is moved relative to said test
14 surface and determining the local deformation of said wavefront everywhere
15 corresponding to a sampled location and the position of said output beam with respect to
16 said test surface.

25. (Previously presented) The apparatus of claim 24 wherein said means for generating said output beam comprises a microscope objective lens and further including a telescopic section between said microscope objective lens and said two-dimensional lens array to image said two-dimensional photodetector array into the pupil of said microscope objective lens.

1 26. (Previously presented) Apparatus for automatically measuring the surface
2 properties of optical elements, said apparatus comprising:
3 a support for an element having at least one test surface to be measured;
4 means for generating an output beam having a predetermined wavefront profile;
5 means for controllably positioning said output beam with respect to said support
6 so that said predetermined wavefront profile thereof impinges on said element from a
7 predetermined direction and then is reflected to travel opposite said predetermined
8 direction as a distorted wavefront containing distortions that vary in accordance with the
9 topography of said test surface and the position of said output beam; and
10 means for sampling said distorted wavefront profile at predetermined locations
11 thereover as said output beam is moved relative to said test surface and determining the
12 local deformation of said wavefront everywhere corresponding to a sampled location and
13 the position of said output beam with respect to said test surface, said means for
14 sampling said distorted wavefront profile comprising a two-dimensional lenslet array
15 having a focal plane and a one-dimensional photodetector array arranged to scan across
16 said focal plane.